





NOTES/SPECIFICATIONS:

- DESIGN WAVELENGTH: 352nm
 CLEAR APERTURE: >80% DIAMETER
 DIAMETER TOLERANCE: +0.0 / -0.1mm
 THICKNESS TOLERANCE: ±0.2mm
 SURFACE FLATNESS: \(\lambda\)/10 AT 632.8nm OVER CLEAR APERTURE
 SURFACE QUALITY: 10-5 SCRATCH-DIG
 BACK SURFACE: FINE GROUND
 PARALLELISM: ≤ 3arcmin
 DURABILITY: MIL-C-675
 COATING: REFLECTIVE COATING
 Ravg>99.5%
 AOI: 0°

FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES

DRAWING PROJECTION			THOR LABS.com		
	NAME	DATE	Ø25.4mm XeF EXCIMER MIRROR		R
DRAWN	BAG	22/OCT/10	$\lambda = 352$ nm, 0° AOI		•
APPROVAL	PM	27/OCT/10			REV
COPYRIGHT © 2010 BY THORLABS			FUSED SILICA		С
VALUES IN PARENTHESIS ARE CALCULATED AND MAY CONTAIN ROUNDOFF ERRORS			NB1-H09	APPROX WE 0.007	ight kg